

#### National Kaohsiung First University of Sci. & Tech.

#### LIGA 技術

#### **LIGA Technology**

#### 余 志 成 高雄第一科技大學機械系

Department of Mechanical and Automation Engineering National Kaohsiung First University of Science and Technology

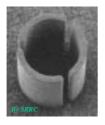
Micro-Electro-Mechanical System Lab





#### What is LIGA?

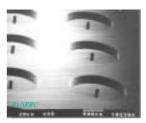
■ German acronym: Lithographie, Gaivanoformung, Abformung (Lithography微影、 Electroplating電鑄、 Molding模造) X光深刻模造法



Lithography



**Electroplating** 



Molding

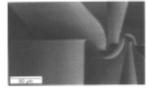




### Why LIGA?

- 80年代發展於Research Center Karlsruhe用來作製造濃縮鈾所需 的擴散噴嘴
- 可製作高度達數百微米,而側面 尺寸可達0.2微米之微元件
- 可用於矽基製程無法製造之金屬 件,或作為塑膠、陶瓷元件之成 形模具
- 缺點:需以X-ray作為曝光源,製 作成本高







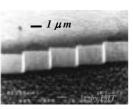


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### Why "LIGA"?



mass production



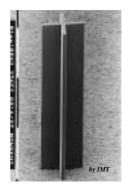
• high precision • low surface roughness



any materials

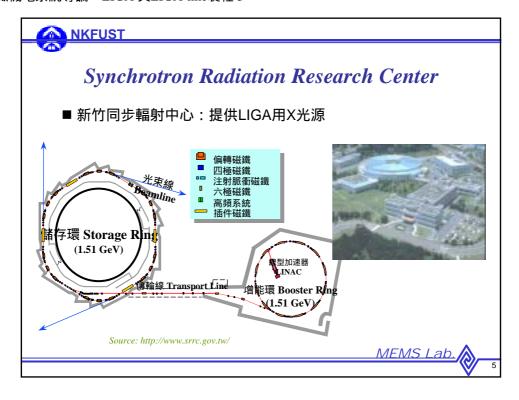


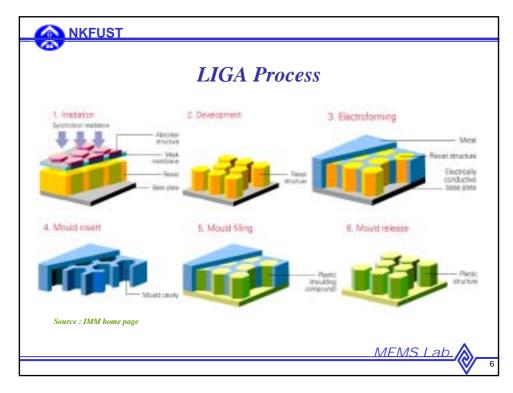
• any lateral pattern



• high aspect ratio





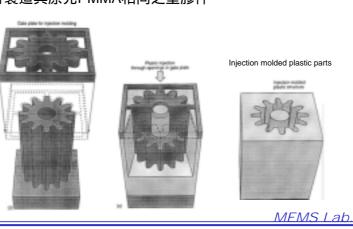






### LIGA (微影電鑄與模造)

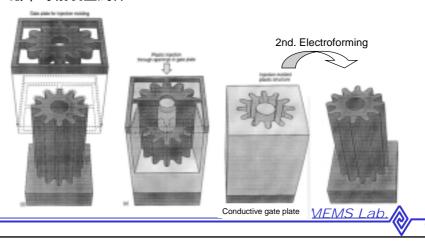
■ X光微影、電鑄、洗去光阻後所得的金屬結構做為射出模具 ,可製造與原先PMMA相同之塑膠件





### LIGA塑模二次翻鑄

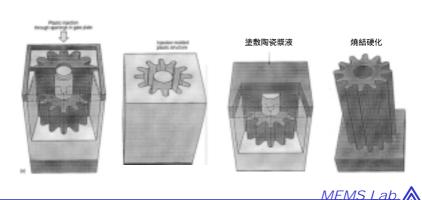
■ 以先前的微射出模具,將塑膠射於導電基版上,進行二次電 鑄,可複製金屬件

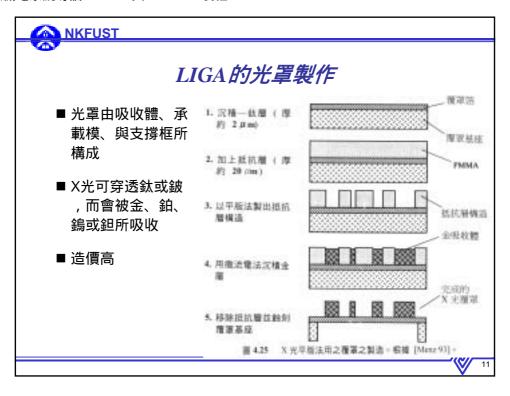


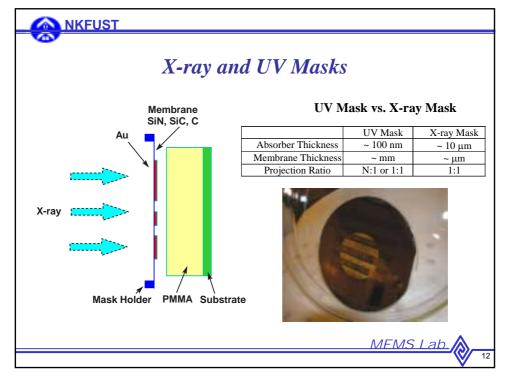


#### 陶瓷材料的微模造

■ 以先前LIGA翻模射出的塑膠模版為基本,充填陶瓷漿液, 再進行燒結,即可得微陶瓷結構



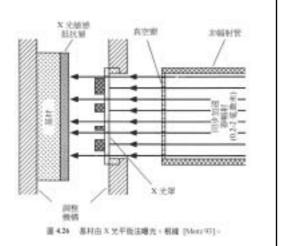




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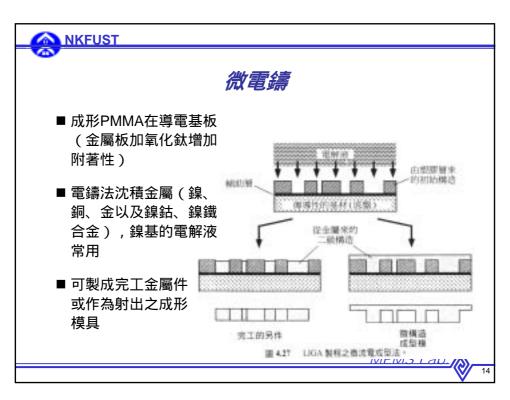
#### X-Ray Lithography

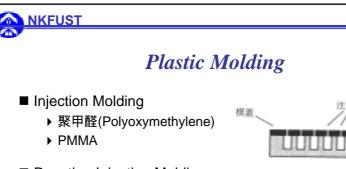
- Fresnel繞射現象會使曝 光源擴散到吸收體邊腳的 非曝光區,造成影像失真 ,繞射現象與波長呈正比
- 同步輻射源X光:磁場加速電子,波長0.2 0.6奈米,平行度佳、穿透性高
- 一般PR採PMMA,但 PMMA對X光不很敏感, 照射時間久(350微米需 八小時),易劣化



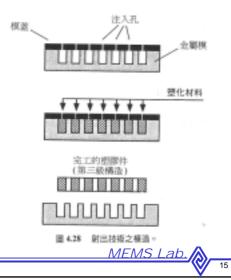
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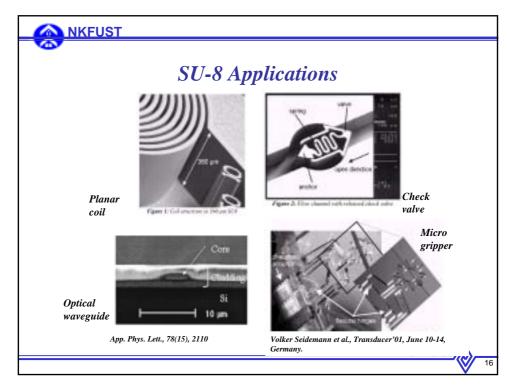
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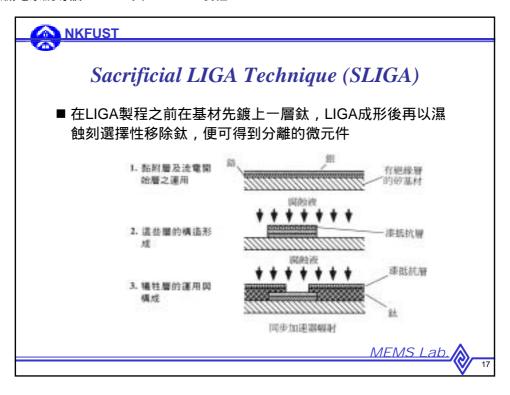


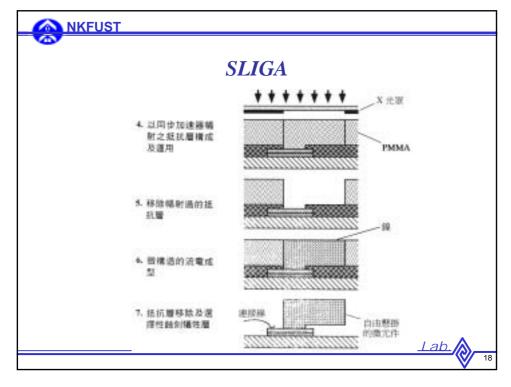


- Reaction Injection Molding
  - ▶ 低黏性、所需壓力低,故較 常用
  - ▶ 使用反應樹脂如甲基丙烯酸 膠、矽膠、乙內醯胺膠
- 成形塑膠件可進行第三級的微 電鑄成金屬件,或以陶瓷粉末 注入塑膠模後燒結成陶瓷件







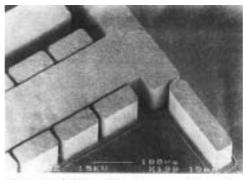


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### 電容式微加速度計之位移感測器

- 鎳製振動質塊,高100微米與上下電極間隙為3微米
- 右下方為mechanical over load stop以防止過載破壞



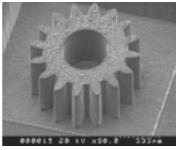
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## <u>NKFUST</u>

#### 微渦輪機的致動齒輪

■ 以LIGA技術製作的鎳齒輪,直徑260微米,高150微米(左圖)





http://ultra10.pidc.gov.tw/Research/Nano/index.html

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#### 具齒輪變速器之微馬達

■ 鎳製,高100微米,軸與轉子間隙為500(nm)



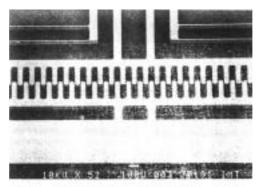
圖 433 使用 SLIGA 技術的個馬達 > 感謝 (4) University of Wisconsin-Madams (Depresest of Elactrical and Computer Sci-

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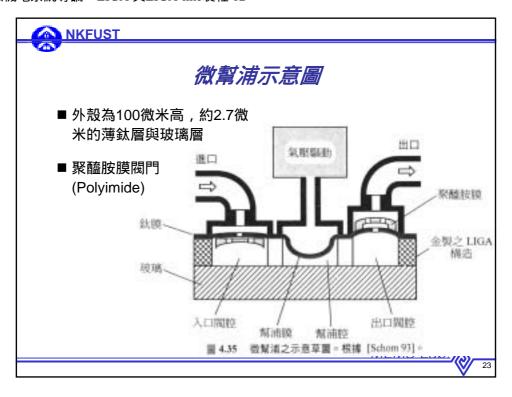


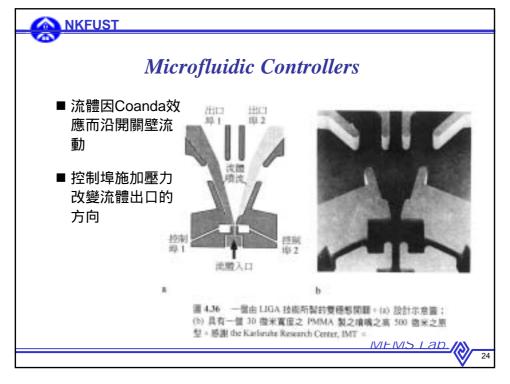
#### Electrostatic Comb Actuators

- 下方梳狀結構與基材連接,上方梳狀結構為懸浮與一微彈簧 結構連接,可受靜電力吸引而移動
- 梳尺長200微米 寬20微米 齒間距5微米
- 結構高70微米



置 4.34 具地狀學動物之 LKIA 微模道。感謝 the Karlarahe Research Center, IMT =







# High Pass Optical Filter

- LIGA technique by reaction molding
- 孔徑80微米,高170微米,間隙8微米

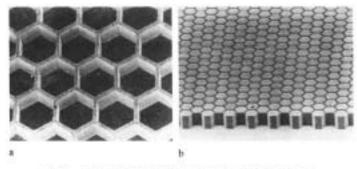


图 4.37 LIGA 製成之高速建光器 □ (a) 鍵模:(b) PMMA 製菓三 級機構造 - 感謝 the Karlsruhe Research Center, IMT -







#### LIGA-like 製程

#### ■ LIGA製程

- ▶ X光深刻模造技術,深度可達數mm,深寬比可大於100,線 寬控制在0.2微米,但成本高
- LIGA-like製程:以其他技術完成光刻微影製程的製程之統稱
  - ▶ 超導小型同步輻射:光源波長1.3nm,曝光深度可達150微米
  - ▶ 深紫外光刻術:光波長為200-300nm之深紫外光,曝光深度 為數百微米,深寬比5-10
  - ▶ 準分子雷射(Excimer Laser)剝蝕:直接在基材上加工,加工 精度在微米級,深寬比10左右,又稱Laser-LIGA
  - ▶ 反應式離子蝕刻(RIE): 蝕刻深度可達500微米,深寬比15-20 左右

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